

SEP-19-02 THU 08:54 AM SHARP PATENTS

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AMENDMENT TRANSMITTAL LETTER (Large Entity)
Applicant(s): Apostolos Voutsas

Docket No.
SLA0592

Serial No 09/893,866	Filing Date June 28, 2001	Examiner Asok K. Sarkar	Group Art Unit 2829
Invention: Method for Forming Silicon Films with Trace Impurities			

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Transmitted herewith is an amendment in the above identified application.

The fee has been calculated and is transmitted as shown below.

TECHNOLOGY CENTER 2800

CLAIMS AS AMENDED

	CLAIMS REMAINING AFTER AMENDMENT	HIGHEST # PREV. PAID FOR	NUMBER OF EXTRA CLAIMS PRESENT	RATE	ADDITIONAL FEE
TOTAL CLAIMS	25 -	23 =	2	x \$18.00	\$36.00
INDEP. CLAIMS	3 -	3 =	0	x \$84.00	\$0.00
Multiple Dependent Claims (check if applicable) _____					
TOTAL ADDITIONAL FEE FOR THIS AMENDMENT					\$36.00

 No additional fee is required for amendment. Please charge Deposit Account No. 19-1457 in the amount of \$36.00.

A duplicate copy of this sheet is enclosed.

 A check in the amount of _____ to cover the filing fee is enclosed. The Commissioner is hereby authorized to charge payment of the following fees associated with this communication or credit any overpayment to Deposit Account No. 19-1457.

A duplicate copy of this sheet is enclosed.

 Any additional fees required under 37 C.F.R. 1.16. Any patent application processing fees under 37 C.F.R. 1.17.

Dated: SEPTEMBER 19, 2002

David C. Ripma, Reg. No. 27,672

David C. Ripma, Reg. No. 27,672

I hereby certify that this correspondence is being facsimile transmitted to the United States Patent and Trademark Office under 37 C.F.R. §1.8 at Fax No. (703) 872-9318 on July 30, 2002.

Note: Each paper must have its own certificate of transmission, or this certificate must identify each submitted paper. The papers submitted include:

<input checked="" type="checkbox"/> This Amendment Transmittal Letter (Duplicate Attached)	2 page(s)
<input checked="" type="checkbox"/> Response under 37 CFR § 1.111	23 page(s)
<input checked="" type="checkbox"/> Attachments	0 page(s)
<input type="checkbox"/> Petition for Extension of Time under 37 C.F.R. § 1.136 (Duplicate Attached)	page

Total pages, including this Transmittal: 25

#7/B
9-24-2
Robert
A FinalIN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:

Inventors: Apostolos Voutsas

Serial No.: 09/893,866

Filed: June 28, 2001

Title: METHOD FOR FORMING
SILICON FILMS WITH TRACE
IMPURITIESATTORNEY FILE NO.
SLA592Do not
enter
ANS
a/27/02CERTIFICATION UNDER 37 CFR § 1.8

I hereby certify that the documents referred to as enclosed herein are being deposited with the United States Postal Service as first class mail on this date in an envelope addressed to: Assistant Commissioner for Patents, Washington, D.C. 20231.

Date

Signature

9/19/02

David L. Roma
Reg. No. 27,672BOX RESPONSES

Assistant Commissioner for Patents
09/25/2002 JROBERTS 00000001 191457 16936
Washington, D.C. 20231
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AMENDMENT AND REQUEST FOR RECONSIDERATION

In response to a Final Office Action filed July 31, 2002, please accept the following amendments and reconsider.

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SEP 19 2002

IN THE CLAIMS:

TECHNOLOGY CENTER 2800

Please amend claims 6, 9, 19, and 22 as follows.

1. (Unchanged) In the fabrication of liquid crystal displays (LCDs), a method for forming silicon films with a controlled amount of trace impurities, the method comprising:

forming a target including silicon and a first concentration of a first impurity;

supplying a substrate; and